LASER ANNEALING APPARATUS

ABSTRACT

Provided is a laser annealing apparatus capable of reducing irradiation unevenness of laser light caused by a refraction phenomenon of laser light due to fluctuation in the temperature of inert gas.

A laser annealing apparatus 1 includes a gas supply unit 10 for supplying inert gas G to at least a laser irradiation area of a workpiece 7 to be processed, and a gas temperature controller 15 for regulating the temperature of the inert gas G. The gas temperature controller 15 controls the temperature of the inert gas G supplied to the laser irradiation area so as to decrease the temperature difference between the temperature of the inert gas G and the atmospheric temperature of a space (a room R) that is disposed outside the supply area of the inert gas so as to surround the optical path of the laser light.

Fig. 1